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APPLICATION NO.	. F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/812,133		03/29/2004	Long-Sun Huang	DEE-PT161	2167
3624	7590	03/03/2005		EXAMINER	
VOLPE A			MCPHERSON, JOHN A		
UNITED PLAZA, SUITE 1600 30 SOUTH 17TH STREET				ART UNIT	PAPER NUMBER
PHILADEL	PHIA, PA	A 19103		1756	
				DATE MAILED: 03/03/2009	5

Please find below and/or attached an Office communication concerning this application or proceeding.

- 10				
	Applic	ation No.	Applicant(s)	
Office Action Summary		2,133	HUANG ET AL.	`
		ner	Art Unit	
		. McPherson	1756	
The MAILING DATE of this comm Period for Reply	nunication appears on	the cover sheet wit	th the correspondence ad	ldress
A SHORTENED STATUTORY PERIOR THE MAILING DATE OF THIS COMMI - Extensions of time may be available under the provis after SIX (6) MONTHS from the mailing date of this of If the period for reply specified above is less than this If NO period for reply is specified above, the maximu - Failure to reply within the set or extended period for Any reply received by the Office later than three more earned patent term adjustment. See 37 CFR 1.704(UNICATION. sions of 37 CFR 1.136(a). In no communication. ty (30) days, a reply within the m statutory period will apply an reply will, by statute, cause the ths after the mailing date of this	statutory minimum of thirty d will expire SIX (6) MON application to become AB	eply be timely filed (30) days will be considered timel THS from the mailing date of this c ANDONED (35 U.S.C. § 133).	ly. ommunication.
Status				
 Responsive to communication(s) This action is FINAL. Since this application is in condit closed in accordance with the present the present of the present the p	2b)⊠ This action i ion for allowance exce	s non-final. ept for formal matte	· •	e merits is
Disposition of Claims				
4) ☐ Claim(s) 1-23 is/are pending in the day of the above claim(s) 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-23 is/are rejected. 7) ☐ Claim(s) is/are objected to select to reserve the day of the	is/are withdrawn from		-	
Application Papers				
9)☐ The specification is objected to be 10)☑ The drawing(s) filed on 29 March Applicant may not request that any one Replacement drawing sheet(s) included the control of	2004 is/are: a)⊠ accobjection to the drawing(ding the correction is rec	s) be held in abeyan quired if the drawing(ce. See 37 CFR 1.85(a). s) is objected to. See 37 C	FR 1.121(d).
Priority under 35 U.S.C. § 119				
12) △ Acknowledgment is made of a classification of the prior of the prior of the prior of the copies of the prior of the copies of the copie	f: rity documents have t rity documents have t ies of the priority docu ational Bureau (PCT f	peen received. peen received in A prents have been Rule 17.2(a)).	pplication No received in this National	Stage
Attachment(s)		 -		
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Revies Information Disclosure Statement(s) (PTO-144 Paper No(s)/Mail Date 		Paper No(s	ummary (PTO-413))/Mail Date formal Patent Application (PTo 	O-152)

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DETAILED ACTION

Claim Objections

1. Claim 1 is objected to because of the following informalities: in line 4, "siad" should be corrected to --said--. Appropriate correction is required.

Claim Rejections - 35 USC § 112

2. Claims 1-23 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

Claims 1 and 18 each present a method comprising defining a plurality of grating zones and forming layers on said grating zones (see claim 1, lines 12-14 and claim 18, lines 8-10), however in the last step of each claim refers to "said grating zone" (i.e. singular, not plural as in the proceeding steps of the claims). It is not clear if the last step is to be performed only for a single grating zone (as implied by the use of "zone"), or if it is intended to be performed for the previously introduced plurality of grating zones (as implied by the use of "said").

Claims 2-17 and 19-23 are included in this rejection only because they each depend from an indefinite claim.

Claim Rejections - 35 USC § 103

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

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(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Applicant's discussion of the prior art in the specification in view of either one of US 6,238,581 to Hawkins et al. (US '581) or US 2004/0027225 to Lee et al. (US '225). Applicant's discussion of the prior art in the specification substantially teaches the invention as claimed, with the exception that the prior art utilizes aluminum or copper as the material of the sacrifice layer (i.e. corresponding to the layer formed in step c of claim 1 and step b of claim 18, and removed in step j of claim 1 and step g of step 18). See paragraphs [0004] to [0009]. Applicant's discussion of the prior art does not teach utilizing silicon oxide as the material of the sacrifice layer.

US '581 discloses a process for manufacturing an electro-mechanical grating device comprising the steps of depositing and then removing a sacrificial layer, wherein the material of the sacrificial layer is selected from a group including silicon oxide. See the abstract and column 6, lines 42-52. US '225 discloses a method of manufacturing a micro electromechanical differential actuator useful in a system such as a grating modulator, wherein the method comprises depositing a sacrifice layer and later performing structure releasing, wherein the material of the sacrifice layer is silicon oxide. See the abstract and paragraph [0031]. It would have been obvious to one skilled in the requisite art to utilize silicon oxide, as taught by either US '581 or US '225, as the sacrifice layer in Applicant's disclosed prior art process because it is taught that silicon oxide is known in the art as a useful material for a sacrifice layer in a process of

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manufacturing an electromechanical grating device, allowing for the formation and release of an electrically actuated grating device.

4. Claims 1-23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Applicant's discussion of the prior art in the specification in view of either one of US 2004/0224523 to Bae et al. (US '523) or JP 6-343272 (JP '272). Applicant's discussion of the prior art in the specification substantially teaches the invention as claimed, with the exception that the prior art utilizes aluminum or copper as the material of the sacrifice layer (i.e. corresponding to the layer formed in step c of claim 1 and step b of claim 18, and removed in step j of claim 1 and step g of step 18). See paragraphs [0004] to [0009]. Applicant's discussion of the prior art does not teach utilizing silicon oxide as the material of the sacrifice layer.

US '523 discloses a method of fabricating micro-electromechanical systems utilizing a sacrificial layer, wherein the material of the sacrificial layer is selected from a group including silicon oxide and copper. See the abstract and paragraph [0017]. JP '272 discloses a method for the manufacture of a micromachine comprising uniformly forming a sacrificial layer, wherein the material of the sacrificial layer is selected from silicon oxide or aluminum. See the abstracts. It would have been obvious to one skilled in the requisite art to utilize silicon oxide, as taught by either US '523 or JP '272, as the sacrifice layer in Applicant's disclosed prior art process because it is taught that silicon oxide is an art-recognized alternative to either copper or aluminum as the material of a sacrifice layer in a process of fabricating a micro-electromechanical system.

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5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to John A. McPherson whose telephone number is (571) 272-1386. The examiner can normally be reached on Monday through Friday, 8:00 AM to 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

John A McPherson Primary Examiner Art Unit 1756

JAM 2/26/05